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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/748,855	12/29/2003	Sang-II Han	8107-1 (S03US005)	6428
75	590 06/22/2005		EXAM	INER
Frank Chau			KIM, PETER B	
F. CHAU & AS	SSOCIATES, LLP		<u> </u>	
Suite 501			ART UNIT	PAPER NUMBER
1900 Hempstead Turnpike			2851	
East Meadow, NY 11551			DATE MAILED: 06/22/2005	

Please find below and/or attached an Office communication concerning this application or proceeding.

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	Application No.	Applicant(s)	-1.0
	10/748,855	HAN, SANG-IL	
Office Action Summary	Examiner	Art Unit	
	Peter B. Kim	2851	
The MAILING DATE of this communication app	ears on the cover sheet with the	correspondence address	
Period for Reply	/ IC CET TO EVOIDE A MONTH	VO) EDOM	
A SHORTENED STATUTORY PERIOD FOR REPLY THE MAILING DATE OF THIS COMMUNICATION. - Extensions of time may be available under the provisions of 37 CFR 1.1: after SIX (6) MONTHS from the mailing date of this communication. - If the period for reply specified above is less than thirty (30) days, a reply If NO period for reply is specified above, the maximum statutory period v - Failure to reply within the set or extended period for reply will, by statute, Any reply received by the Office later than three months after the mailing earned patent term adjustment. See 37 CFR 1.704(b).	36(a). In no event, however, may a reply be ti y within the statutory minimum of thirty (30) da vill apply and will expire SIX (6) MONTHS from , cause the application to become ABANDON	imely filed ys will be considered timely. In the mailing date of this communication (SS U.S.C. § 133).	ion.
Status			
1) Responsive to communication(s) filed on	<u>_</u> .		
2a) This action is FINAL . 2b) ☑ This	action is non-final.		
3) Since this application is in condition for allowar	nce except for formal matters, pr	osecution as to the merits	is
closed in accordance with the practice under E	Ex parte Quayle, 1935 C.D. 11, 4	53 O.G. 213.	
Disposition of Claims			
4) Claim(s) 1-20 is/are pending in the application.			
4a) Of the above claim(s) is/are withdraw	wn from consideration.		
5) Claim(s) is/are allowed.			
6)⊠ Claim(s) <u>1-20</u> is/are rejected.			
7) Claim(s) is/are objected to.			
8) Claim(s) are subject to restriction and/o	r election requirement.		
Application Papers			
9)☐ The specification is objected to by the Examine	r.		
10)☐ The drawing(s) filed on is/are: a)☐ acce	epted or b) objected to by the	Examiner.	
Applicant may not request that any objection to the	drawing(s) be held in abeyance. Se	e 37 CFR 1.85(a).	
Replacement drawing sheet(s) including the correct		•	
11) The oath or declaration is objected to by the Ex	aminer. Note the attached Office	e Action or form PTO-152.	
Priority under 35 U.S.C. § 119			
12) △ Acknowledgment is made of a claim for foreign a) △ All b) ☐ Some * c) ☐ None of: 1. △ Certified copies of the priority documents 2. ☐ Certified copies of the priority documents 3. ☐ Copies of the certified copies of the priority	s have been received. s have been received in Applicat rity documents have been receiv	tion No	
application from the International Bureau	` ` ' '		
* See the attached detailed Office action for a list	or the certified copies not receiv	ea.	
Attachment(s)			
1) Notice of References Cited (PTO-892)	4) Interview Summar		
 Notice of Draftsperson's Patent Drawing Review (PTO-948) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08) Paper No(s)/Mail Date 122003, 22004. 	Paper No(s)/Mail D 5) Notice of Informal 6) Other:	Date Patent Application (PTO-152)	

DETAILED ACTION

Claim Rejections - 35 USC § 102

The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

(b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.

Claims 1-20 are rejected under 35 U.S.C. 102(b) as being anticipated by Kawakubo (6,219,130).

Kawakubo discloses a method for overlay measurement using a multiplex filter, comprising: selecting a first filter from a plurality of filters and positioning the first filter underneath a lens of an overlay measurement apparatus; determining whether overlay marks formed on a wafer are perceptible through the lens and the first filter; measuring the overlay marks if the overlay marks are perceptible; and replacing the first filter with a second filter from the plurality of filters if the overlay marks are not perceptible through the first filter (col. 5, line 50 – col. 6, line 10, col. 9, lines 20-32).

Kawakubo discloses a method for overlay measurement, comprising: selecting a first filter from a plurality of filters and positioning the first filter on an overlay measurement apparatus; determining whether overlay marks formed on a semiconductor surface are able to be measured using the first filter; measuring the overlay marks if the overlay marks are able to be measured; and replacing the first filter with a second filter from the plurality of filters if the overlay marks are not able to be measured using the first filter (col. 5, line 50 – col. 6, line 10, col. 9, lines 20-32).

Kawakubo discloses a method for overlay measurement, comprising: using a plurality of filters in conjunction with an overlay measurement apparatus to perceive overlay marks on a semiconductor surface; and measuring perceptible overlay marks (col. 5, line 50 – col. 6, line 10, col. 9, lines 20-32).

Kawakubo discloses analyzing the overlay marks and calculating the results of the analysis (col. 6, line 48- col. 7, line 5). Kawakubo also discloses filter including red, yellow and green filters (col. 7, lines 23-42).

Claims 1-3, 13, 19 and 20 are rejected under 35 U.S.C. 102(b) as being anticipated by Mishima (6,151,121).

Mishima discloses a method for overlay measurement using a multiplex filter, comprising: selecting a first filter from a plurality of filters and positioning the first filter underneath a lens of an overlay measurement apparatus; determining whether overlay marks formed on a wafer are perceptible through the lens and the first filter; measuring the overlay marks if the overlay marks are perceptible; and replacing the first filter with a second filter from the plurality of filters if the overlay marks are not perceptible through the first filter (col 7. lines 43-62 and col. 8, lines 1-16).

Mishima discloses a method for overlay measurement, comprising: selecting a first filter from a plurality of filters and positioning the first filter on an overlay measurement apparatus; determining whether overlay marks formed on a semiconductor surface are able to be measured using the first filter; measuring the overlay marks if the overlay marks are able to be measured; and replacing the first filter with a second filter from the plurality of filters if the overlay marks

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are not able to be measured using the first filter (col 7. lines 43-62 and col. 8, lines 1-16).

Mishima discloses a method for overlay measurement, comprising: using a plurality of filters in conjunction with an overlay measurement apparatus to perceive overlay marks on a semiconductor surface; and measuring perceptible overlay marks (col 7. lines 43-62 and col. 8, lines 1-16).

Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Peter B. Kim whose telephone number is (571) 272-2120. The examiner can normally be reached on 8:00 AM - 5:30 PM.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Judy Nguyen can be reached on (571) 272-2258. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Peter B. Kim Primary Examiner

The Blim

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